Fabrication of PDMS soft stamps for nanoimprint lithography (NIL)

J. Pradyumna*, K. Shashank Kumar, Sanjana S. Kanguri, P. Bharath

Central Manufacturing Technology Institute, Bengaluru, Karnataka, India

KEYWORDS

Polydimethylsiloxane (PDMS),
Nanoimprint Lithography (NIL),
Micro-Engineering,
Soft Lithography,
Soft Stamps.

ABSTRACT

Polydimethylsiloxane (PDMS) elastomers are widely utilized for replicating microstructures in microfluidic and micro-engineering applications using. This study presents a method for fabricating polydimethylsiloxane (PDMS) soft stamps utilized for nanoimprint lithography (NIL). PDMS is favoured due to its mechanical properties, ease of fabrication, and compatibility with various substrates. The study investigates the fabrication process, challenges regarding durability, and implications for pattern fidelity in NIL applications and assess the quality of these stamps based on pattern accuracy and replication precision showcasing their possible uses in nanotechnology and microfabrication. The results indicate that PDMS soft stamp demonstrates excellent flexibility and conformability, enabling effective imprinting onto various substrates which can be used as a feasible option for scalable and cost-efficient NIL procedures.

1. Introduction

Nanoimprint lithography (NIL) has emerged as a transformative nanofabrication technique, enabling the creation of nanoscale patterns with exceptional precision and resolution. Unlike traditional photolithography, which relies on complex optical systems, NIL employs a straightforward mechanical process to transfer nanoscale patterns from a mold or stamp to a substrate. This unique approach not only simplifies the fabrication process but also makes NIL highly cost-effective and suitable for producing complex nanostructures with high fidelity. The ability to pattern a wide variety of materials with sub-10 nm resolution has positioned NIL as a pivotal tool in fields ranging from electronics and photonics to biotechnology and materials science. A critical component in NIL is the imprinting stamp, which plays a central role in the fidelity and efficiency of the pattern transfer process. Among the materials used for soft stamps, polydimethylsiloxane (PDMS) has garnered significant attention due to its distinctive mechanical, chemical, and optical properties. PDMS is a silicone elastomer that exhibits remarkable flexibility and elastomeric behavior, allowing it to achieve intimate conformal contact with the substrate. This ensures uniform pressure distribution during the imprinting process, which is essential for high-quality pattern replication. Moreover, the inherent softness and flexibility of PDMS enable it to adapt to uneven or non-planar surfaces, minimizing defects and enhancing the fidelity of the transferred patterns. PDMS also offers several additional advantages that make it particularly suitable for NIL applications. Its excellent optical transparency in the UV-visible range makes it compatible with UV-assisted NIL processes. Furthermore, PDMS is biocompatible, chemically stable, and relatively easy to fabricate into stamps of various shapes and sizes. These attributes, combined with its versatility and cost- effectiveness, have driven its widespread adoption in NIL, particularly for applications that demand high resolution and defect-free patterning.

This study aims into the detailed fabrication process of PDMS soft stamps and explore their mechanical properties. By characterizing the performance of PDMS stamps in NIL applications, the research seeks to provide insights into optimizing their use for a diverse range of substrates and patterning requirements. The findings of this study could pave the way for further advancements in NIL, contributing to its broader adoption across industries that rely on nanoscale precision and efficiency.

*Corresponding author E-mail: pradyumna@cmti.res.in

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2. Materials and Methods

The primary material used is polydimethylsiloxane (PDMS), specifically the Sylgard 184 kit, which comprises a base and a curing agent. Additional materials include master mold, photo resists for lithography, and solvents for cleaning processes such as Acetone, Iso-propanol and Deionised water.

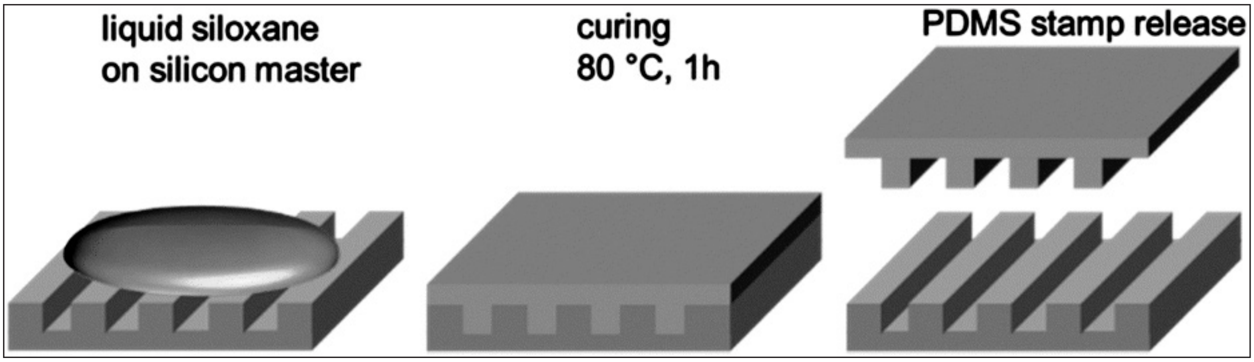
2.1. Fabrication process

- **PDMS mixture preparation**

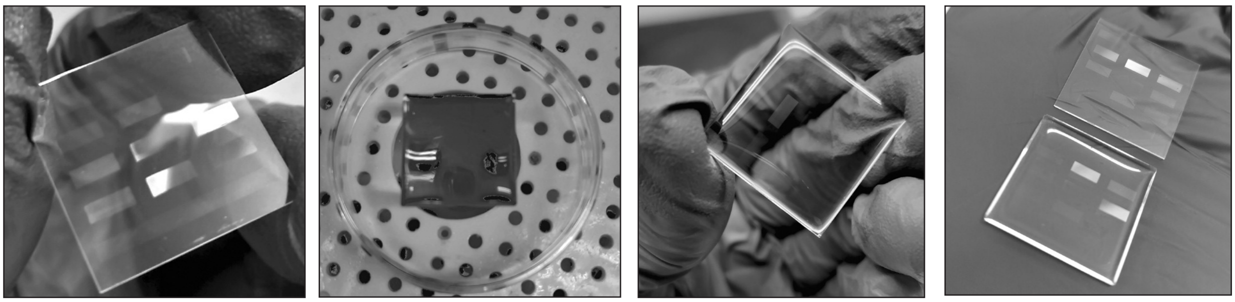
The fabrication of polydimethylsiloxane (PDMS) soft stamps begins with the preparation of the PDMS mixture, which involves combining the pre-polymer base with the curing agent at a precise weight ratio of 10:1. This ratio is critical to achieving the desired mechanical properties, such as flexibility and durability, in the final PDMS stamp. Once the components are thoroughly mixed, the resulting liquid is subjected to a degassing process in a vacuum chamber. This step is essential to eliminate trapped air bubbles that may form during mixing, as these bubbles could compromise the surface uniformity and structural integrity of the stamp. The degassing process ensures a smooth, defect-free surface, which is crucial for high-fidelity pattern transfer during nanoimprint lithography (NIL). The resulting PDMS material exhibits homogeneity, making it well-suited for achieving intimate conformal contact with substrates and producing consistent nanoscale patterns with minimal defects.

- **Stamp fabrication**

The next step in the fabrication process involves transferring the degassed PDMS mixture onto a master mold, which contains the desired nanoscale patterns. The liquid PDMS is carefully poured over the mold and evenly distributed to ensure complete coverage and uniform thickness across the entire surface. This meticulous step is crucial for maintaining the fidelity of the pattern replication. Once the PDMS is evenly spread, the entire assembly is placed in an oven set at 80°C to initiate the curing process. The curing duration typically ranges from 8 to 10 minutes, though it may vary depending on the surface area and complexity of the master mold. Larger or more intricate molds may require slight adjustments to the curing time to ensure the PDMS fully hardens without compromising pattern fidelity. Upon completion of the curing process, the hardened PDMS material is carefully separated from the master mold. This peeling step demands precision and delicacy to preserve the intricate designs imprinted on the PDMS surface.



Courtesy: F. M. Wisser, et al (2015). "Precursor strategies for metallic nano- and micropatterns using soft lithography". Royal Society of Chemistry.



(a) (b) (c) (d)

Fig. 1. (a) Master Stamp, (b) Degassing PDMS, (c) Cured PDMS, (d) Peeled PDMS.

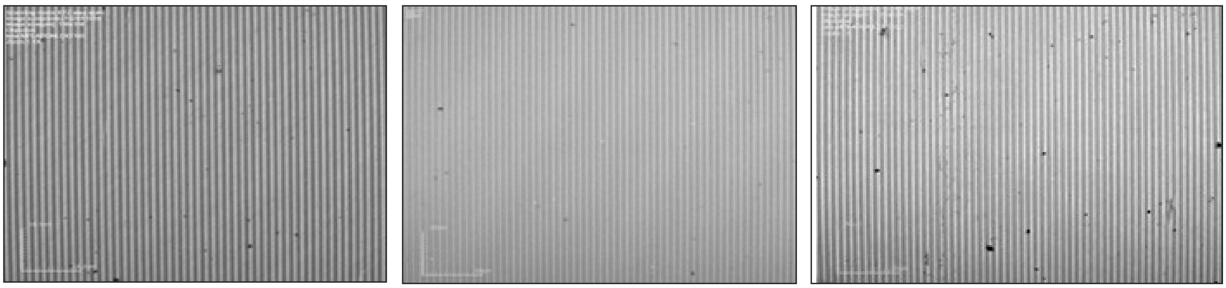
The flexibility and elastomeric nature of PDMS facilitate this process, allowing the stamp to retain the exact features of the original mold with high resolution and minimal distortion. The resulting PDMS stamp is now ready for application in nanoimprint lithography (NIL), offering exceptional pattern fidelity and adaptability for high-precision nanoscale fabrication.

2.2. Characterization of PDMS stamps

To evaluate the fidelity and effectiveness of the fabricated PDMS soft stamps, advanced imaging techniques are employed. Confocal microscopy serves as a primary tool to assess the accuracy of pattern transfer from the master mold to the PDMS stamp. The high-resolution confocal images provide clear visual evidence of successful pattern replication, confirming that the intricate nanoscale designs of the master mold are precisely transferred onto the soft stamp. Furthermore, the imaging demonstrates the capability of the PDMS stamp to effectively transfer these patterns onto nanoimprint lithography (NIL) resists, maintaining high fidelity throughout the process. To achieve a more detailed evaluation of pattern quality and transfer accuracy, optical microscopy is utilized. optical microscopy provides superior spatial resolution and depth of field, enabling a comprehensive analysis of the structural integrity and uniformity of the transferred patterns. By comparing optical microscopy images of the master mold, PDMS soft stamp, and NIL resist patterns, the overall effectiveness and consistency of the pattern replication process can be quantitatively and qualitatively assessed. These imaging techniques not only validate the performance of the fabricated PDMS soft stamps but also identify any potential defects or deviations, offering insights for optimizing the fabrication and imprinting processes. From figure 2 shows pattern reproducibility from a) master stamp to b) PDMS soft stamp to c) Pattern Transfer to NIL and confocal microscopy image from figure 3 shows that accurate pattern fidelity and pattern transfer from a) master stamp to b) PDMS soft stamp to c) Pattern Transfer to NIL.

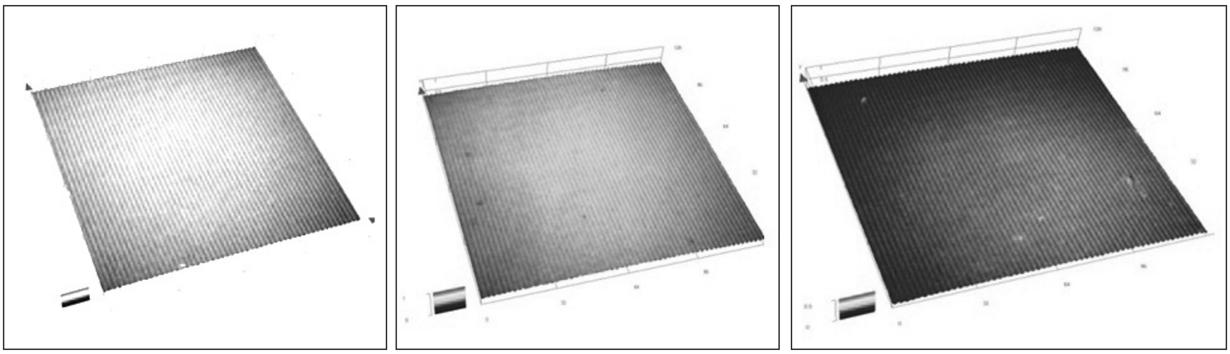
3. Results & Discussion

The experimental results underscore the significant advantages of using PDMS soft stamps in nanoimprint lithography (NIL) processes. Key benefits include their exceptional conformability to various substrates, ease of fabrication, and the ability to achieve high-resolution pattern replication. The results obtained from confocal microscopy validate the pattern fidelity of the PDMS stamps, demonstrating their ability to



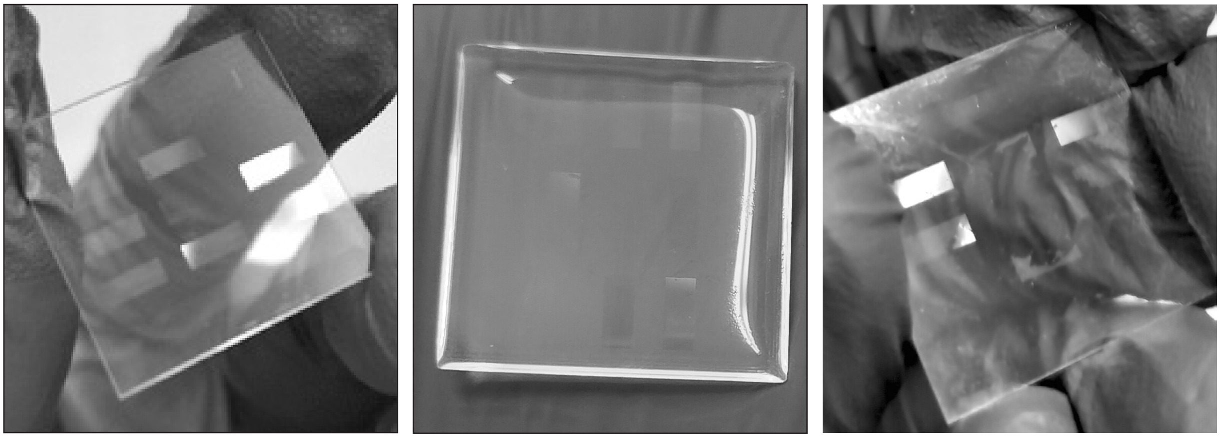
(a) (b) (c)

Fig. 2. (a) Master stamp 2D image, (b) PDMS soft stamp 2D image, (c) Pattern transfer to NIL resist 2D image.



(a) (b) (c)

Fig. 3. (a) Master stamp, (b) PDMS soft stamp 3D image, (c) Pattern transfer to NIL resist 3D image.



(a) (b) (c)

Fig. 4. (a) Master stamp, (b) PDMS soft stamp, (c) Pattern transfer to NIL resist.

Table 1
Confocal microscopy characterization results.

Sl.No		Master Stamp (µm)	PDMS Soft Stamp (µm)	NIL Sample (µm)
1.	Width	0.085	0.080	0.093
	Depth	1.496	1.313	1.167
	Period	2.367	2.229	2.167
2.	Width	0.063	0.068	0.090
	Depth	0.833	0.938	0.833
	Period	1.496	1.396	1.396
3.	Width	0.078	0.106	0.084
	Depth	2.208	2.021	2.021
	Period	3.917	3.896	3.854
4.	Width	0.045	0.036	0.065
	Depth	4.792	4.208	4.854
	Period	9.833	9.604	9.521

accurately replicate nanoscale features from the master mold. Furthermore, the subsequent transfer of these patterns from the PDMS soft stamp to the NIL resist was also confirmed to be precise and reproducible, highlighting the potential of PDMS stamps for use in advanced NIL applications. Despite these successes, challenges remain, particularly in the durability and wear resistance of PDMS stamps during repeated imprinting cycles. As PDMS is inherently soft and elastomeric, repeated mechanical stress and adhesion to NIL resists can lead to wear, deformation, or degradation of the stamp over time. This issue has been identified as a critical limitation for the widespread adoption of PDMS stamps in industrial-scale NIL processes. To address this, surface modification techniques such as silanization can been explored. Silanization treatments have been shown to enhance the hydrophobicity of PDMS surfaces, thereby reducing adhesion to NIL resists and minimizing wear. For instance, Zhou et al. (2010) recent developments in PDMS surface modification for microfluidic devices". Electrophoresis. have demonstrated that these surface treatments not only improve the performance of PDMS stamps but also significantly extend their operational lifespan. However, the implementation of these treatments requires further optimization to balance cost, scalability, and performance improvements. Parameters such as the curing conditions, degassing efficiency, and master mold design could be fine-tuned to achieve better consistency and reliability in stamp fabrication. From Figure 4 (b) PDMS Soft Stamp to NIL Resist show fabricated PDMS Soft Stamp and pattern from PDMS soft stamp to NIL Resist. From Table 1 the results of Confocal Microscopy measurements quantitatively shows and which ensures accurate pattern fidelity and reproducibility from (a) Master Stamp, to (b) PDMS Soft Stamp,and to (c) Pattern Transfer to NIL Resist. The integration of PDMS-based NIL technologies holds tremendous potential across a variety of applications, including microelectronics, biomedicine, and advanced optics.

4. Conclusion

This study provides a detailed and comprehensive overview of the fabrication and characterization of polydimethylsiloxane (PDMS) soft stamps for nanoimprint lithography (NIL). The findings highlight the remarkable potential of PDMS as a soft stamp material, offering a unique combination of cost-effectiveness, ease of fabrication, and suitability for large-scale applications. The study demonstrates that PDMS soft stamps are capable of achieving high-fidelity pattern transfer from master molds to NIL resists, showcasing their effectiveness in enabling precise nanoscale fabrication. The flexibility, conformability, and optical transparency of PDMS stamps make them particularly advantageous for a broad range of NIL applications. These attributes, coupled with their low production cost, position PDMS stamps as a practical solution for industries requiring advanced nanofabrication techniques. However, challenges such as limited durability and wear during repeated imprinting cycles must be addressed to unlock their full potential. Surface modifications, such as silanization, have shown promise in mitigating these issues, paving the way for further enhancements in stamp performance and longevity Looking ahead, continued research is essential to optimize the fabrication processes and develop strategies to improve the mechanical properties and durability of PDMS stamps. Exploring alternative elastomers or hybrid materials that retain the advantageous properties of PDMS while offering improved resistance to wear and deformation could significantly broaden the applicability of NIL technologies. Additionally, efforts to scale up the production of PDMS stamps while maintaining precision and quality will further enhance their adoption across diverse technological domains. PDMS-based NIL technologies hold immense promise for advancing applications in microelectronics, biomedicine, photonics, and beyond. By overcoming current challenges and refining these methodologies, PDMS stamps can play a pivotal role in driving innovations in nanoscale fabrication. The insights gained from this study contribute to the growing body of knowledge in NIL and underscore the potential of PDMS as a cornerstone material for next-generation nanofabrication techniques.

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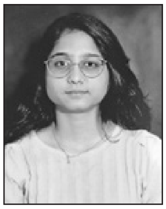
J. Pradyumna is a Scientist at Central Manufacturing Technology Institute, Bengaluru. He has done post graduation (M.Tech) in Machine Design from SJCIT, Chikkaballapur. He has over 10 years of Professional experience in the field of Design & Development of subsystems for Machine Vision, Product design for various In house & customer requirement, Designing of MEMS Sensors, Development of Bio Medical devices, MEMS Fabrication process & Micro System Packaging processes. He has published over 5 publications in National / International Journals & Conferences.

K. Shashank Kumar presently working at Central Manufacturing Technology Institute, Bangalore as Project Associate. He has done B.E in Mechanical Engineering from RNS Institute of Technology, Bangalore in 2023.He is currently working in the field of Semiconductor Technology and interested in Nano technology, Photovoltaics and fabrication of semiconductor devices.
(E-mail: shashankkumar.pro@gmail.com)



Sanjana S. Kanguri, working at Central Manufacturing Technology Institute, Bangalore as Project Associate. She has done her B.Sc in Genetics, Biotechnology, Biochemistry from Padmashree Institute of Management and Sciences, Bangalore in 2021. She has done her Masters in Biotechnology from Maharani Lakshmi Ammanni College for Women, Bangalore in 2023. She is currently working in the field of Biomedical devices and interested in the field of Biotechnology.
(E-mail: sksanjana38@gmail.com)

P. Bharath is presently working at Central Manufacturing Technology Institute, Bengaluru as a Project Associate. He done B.Tech in Mechanical Engineering from Government Engineering College, Chamarajanagar in 2021. He is currently working in the field of MEMS technologies and Interested in the field of Semiconductors, New Product Design, Analysis and fabrication of MEMS devices.
(E-mail: devangbharath550@gmail.com)